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Client Matter No. 81848.0016.001  
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

<p>Serial No. 09/546,174</p> <p>Application of: Chih-Chien Liu, Ta-Shan Tseng, W. B. Shieh, J. Y. Wu, Water Lur and Shih-Wei Sun</p> <p>Filed: April 11, 2000</p> <p>Art Unit: 1711</p> <p>Examiner: Sergeant, Rabon A.</p> <p>Attorney Docket No. UMC-96-279 CON</p> <p>For: HIGH DENSITY PLASMA CHEMICAL VAPOR DEPOSITION PROCESS</p>	<p>Confirmation No.: 4793</p> <p>Customer No.: 25235</p>
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AMENDMENT AND RESPONSE PURSUANT TO FINAL OFFICE ACTION  
DATED AUGUST 25, 2005

MAIL STOP AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the final office communication mailed August 25, 2005, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 11 of this paper.

11CS - 81848.0016 - 77125-42

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